

IC ANALYSIS SYSTEM HAVING CHARGED
PARTICLE BEAM APPARATUS

ABSTRACT OF THE DISCLOSURE

The object of the invention is to provide an IC
5 analysis system (100) having a charged particle beam
apparatus (300) in which the operability and picture
quality have been enhanced and the measurement method of
a device under test. In the IC analysis system, stop
signal generating means (205) in which the stop signal
10 stimulates the acquisition of image data is added to a
test pattern generator (200) and acquisition completion
signal generating means (308) which releases the stopping
state on completing the acquisition of image data and
which resumes the test pattern updating operation is
15 added to the charged particle beam apparatus.
Furthermore, by adding mode select means (309) to the
charged particle beam apparatus, a clearer potential
contrast image can be obtained. The methods for locating
fault positions can be realized in the IC analysis system
20 having the charged particle beam apparatus wherein the
image data can be obtained by alternate test patterns, or
by adding one image data to the reverse potential of
another image data, or by scanning and irradiating the
charged particle beam onto the same surface of the device
25 at a plurality of times.

Figure 1 to accompany